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INFORMATION DISCLOSURE STATEMENT							1017	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,		
(Use several sheets if necessary)					APPLICANTS Masahiro SAKURADA et al.					
					FILING DATE December 19, 2005			1700-		
U.S. PATENT DOCUMENTS										
EXAMINER INITIAL		DOCUMENT NUMBER	DATE		NAME			CLASS	SUB CLASS	
5H.	1)	5,919,302	0706/1999		FALSTER et al.			_		
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KH.	2)	JP A 2002-057160 w/ abst. & trans	02/	22/2002	JAPAN			_	-	
rH.	3)	JP A 2000-313691 w/ abst. & trans	11/	14/2000	JAPAN			_	1	
FiH.	4)	JP A 11-147786 w/ abstract & trans	06/	02/1999	JAPAN			ı	_	
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EXAMINER John Meh					DATE CO			ONSIDERED		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in										

Date: December 19, 2005